Electronic Supplementary Information (ESI)

Realization of highly photoresponsive azobenzene-functionalized monolayers

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Fig. S1  Changes in the normalized absorbance at $\lambda_{\text{max}}$ of $\pi-\pi^*$ band of (a) MeSH and (b) EtSH in dichloromethane as a function of dark incubation after UV light irradiation. The ratio of the trans form of EtSH was obtained from $^1$H NMR data (in CD$_2$Cl$_2$).

Fig. S2  Changes in $(A_t - A_{ap})$ of cis-EtSH SAMs as a function of thermal cis-to-trans isomerization time after UV light irradiation. $A_{ap}$ and $A_t$ correspond to absorbance at $\lambda_{\text{max}}$ of as-prepared SAMs and after dark incubation for time (t), respectively.